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PATENT APPLICATION  
09/996,333

Receipt



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

6/7/02  
#3/Cfr

In re Application of: Peter Buck  
Serial No.: 09/996,333  
Filing Date: November 28, 2001  
Confirmation No.: 3572  
Title: PHOTOMASK AND METHOD FOR REDUCING  
EXPOSURE TIMES OF HIGH DENSITY PATTERNS  
ON THE SAME

Office of Initial Patent Examination's Customer  
Service Center  
Assistant Commissioner of Patents  
Washington, D.C. 20231

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the date shown below.

*K. Bowma*

Name

Date

4/30/02

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TC 1700

Dear Sir:

REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT

Attached is a copy of the Official Filing Receipt received from the U.S. Patent and Trademark Office in the above-identified patent application for which issuance of a corrected filing receipt is respectfully requested.

The Domestic Priority Data is not listed on the Official Filing Receipt. Please insert -  
THIS APPLN CLAIMS PRIORITY TO 60/253,532 FILED 11/28/2000 AND 60/254,221  
FILED 12/8/2000. Included is Page 1 of the Applications which reflects the priority data. A  
corrected filing receipt is respectfully requested.

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064441.0219

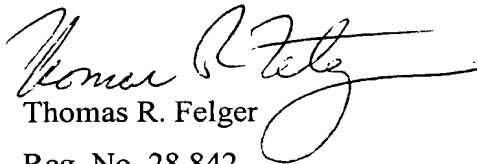
PATENT APPLICATION  
09/996,333

2

While it is believed that this is not an error by the Applicants, the Commissioner is hereby authorized to charge any amount required by this paper or credit any overpayment to Deposit Account No. 02-0384 of Baker Botts L.L.P.

Respectfully submitted this 25<sup>th</sup> day of April, 2002.

BAKER BOTTS L.L.P.  
Attorneys for Applicant

  
Thomas R. Felger  
Reg. No. 28,842

2001 Ross Avenue, Suite 600  
Dallas, Texas 75201-2980  
512.322.2599  
(sds)

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PATENT APPLICATION

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1

PHOTOMASK AND METHOD FOR REDUCING EXPOSURE TIMES  
OF HIGH DENSITY PATTERNS ON THE SAME

CROSS REFERENCE TO RELATED APPLICATION

This application claims priority from U.S.  
Provisional Patent Application Serial No. 60/253,532,  
filed November 28, 2000, and entitled "Strategy to Reduce  
5 Write Times for High Density Mask Layers with Repetitive  
Cell Structure," and U.S. Provisional Patent Application  
Serial No. 60/254,221, filed December 8, 2000, and  
entitled "Method to Reduce Mask Exposure Time for High  
Density Mask Layers with Repetitive Cell Structure and  
10 Optical Proximity Correction."

TECHNICAL FIELD OF THE INVENTION

This invention relates in general to  
photolithography and, more particularly, to a photomask  
15 and method for reducing exposure times of high density  
patterns on the same.

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APPLICATION NUMBER	FILING DATE	GRP ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLAIMS	IND CLAIMS
09/996,333	11/28/2001	1756	878	064441.0219	5	23	4

CONFIRMATION NO. 3572

FILING RECEIPT



\*OC000000007208347\*

Paula D. Heyman  
Baker Botts L.L.P.  
Suite 600  
2001 Ross Avenue  
Dallas, TX 75201-2980

Date Mailed: 12/18/2001

Receipt is acknowledged of this nonprovisional Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Customer Service Center. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Peter Buck, Aloha, OR;

Assignment For Published Patent Application

Dupont Photomasks, Inc.;

Domestic Priority data as claimed by applicant

THIS APPLN CLAIMS PRIORITY TO 60/253,532 FILED 11/28/2000 AND  
60/254,221 FILED 12/8/2000

Foreign Applications

If Required, Foreign Filing License Granted 12/18/2001

Projected Publication Date: Request for Non-Publication Acknowledged

Non-Publication Request: Yes

Early Publication Request: No

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TC 1700

Title

Photomask and method for reducing exposure times of high density patterns on the same

Preliminary Class

430

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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